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PATENT TRADEMARK OFFICE



Patent
Case No.: 58934US002

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

First Named Inventor: LU, DAVID D.
Application No.: 10/645020 Group Art Unit: Unknown
Filed: August 21, 2003 Examiner: Unknown
Title: PHOTOTOOL COATING

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on:

11-25-03
Date

Tom Sanders
Signed by: Tom Sanders

Dear Sir:

Pursuant to 37 CFR §§ 1.56, 1.97, and 1.98, enclosed is a completed Form PTO-1449, citing references submitted for consideration by the Examiner. Copies of any cited foreign patents, non-patent literature, and unpublished US application documents are enclosed. Pursuant to the waiver in the Pre-OG Notice, dated July 25, 2003, copies of US patents and published US patent applications are no longer required and are not enclosed. It is respectfully requested that the Examiner initial and return the enclosed Form PTO-1449 to indicate that each reference has been considered.

It is believed that no fee is due; however, in the event a fee is required, please charge the fee to Deposit Account No. 13-3723.

Respectfully submitted,

Nov. 25, 2003
Date

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Page 1 of 1

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10/645020

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First Named Inventor

Lu, David D.

Art Unit

Examiner Name

Attorney Case Number

58934US002

U.S. Patent Documents

Exam. Init.*	Cite No.	Document Number	Publication Date or Issue Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Doc. Number-(Kind Code if Known)			
	A1	US- 3,810,874	05/1974	Mitsch, et al.	
	A2	US- 4,514,489	04/1985	Garcia et al.	
	A3	US- 4,735,890	04/1988	Nakane	
	A4	US- 5,286,567	02/1994	Kubota et al.	
	A5	US- 5,356,736	10/1994	Kita et al.	
	A6	US- 5,602,225	02/1997	Montagna et al.	
	A7	US- 6,277,485 B1	08/2001	Invie et al.	
	A8	US- 6,300,042 B1	10/2001	Mancini et al.	
	A9	US- 6,387,787 B1	05/2002	Mancini et al.	
	A10	US- App. 10/161,258	05/2002	Boardman, et al.	

Foreign Patent Documents

Exam. Init.*	Cite No.	Foreign Patent Document		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	Translation (Check if yes)
		Ctry. Code	Number-KindCode (If known)				
	B1	EP	0 603 697 B1	03.09.1997	Strepparola, et al.		
	B2						

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Exam. Init.*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published
	C1	C. Tonelli, et al., "Linear perfluoropolyether difunctional oligomers: chemistry, properties and applications", Journal of Fluorine Chemistry 95, 1999, pp. 51-70.
	C2	C. T. Yim et al., "Dynamics of Octadecylphosphonate Monolayers Self-Assembled on Zirconium Oxide: A Deuterium NMR Study", J. Phys. Chem, B 2002, 106, 1728-1733
	C3	D. L. Flowers, "Lubrication in Photolithography", J. Electrochem. Soc.: Solid-State Science and Technology, Vol. 124, October 1977, pp. 1608-1612
	C4	Toshiharu Matsuzawa et al., "Surface Conversion for Antisticking to Reduce Patterning Defects in Photolithography", J. Electrochem. Soc.: Solid-State Science and Technology, Vol. 128, No. 1, January 1981, pp. 184-187.

*Examiner:

Date Considered:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Information Disclosure Statement)